

SEMICONDUCTOR WASTE-GAS TREATING APPARATUS BEING FILTH  
SEDIMENTATION- AND ETCHING-PROOF

ABSTRACT OF THE DISCLOSURE

A semiconductor waste-gas treating apparatus having the ability of  
5 preventing sedimentation and etching of filth, the apparatus comprises a  
header, a waste gas treating trough and an annular guide. The apparatus  
takes advantage of the function that a header generates flame of high  
temperature to catalytically decompose waste gas, and by cooperation  
between an annular guide and a waste gas treating trough, an annular water  
10 wall can be formed on the inner wall a waste gas reacting room to isolate and  
prevent powder and erosive material from contact with the wall of the  
reacting room; thereby, the phenomenon of sedimentation and etching of filth  
in the semiconductor waste-gas treating trough can be eliminated.

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